

Self-modulation doping effect in the high-mobility layered semiconductor  $\text{Bi}_2\text{O}_2\text{Se}$ Huixia Fu,<sup>1</sup> Jinxiong Wu,<sup>2</sup> Hailin Peng,<sup>2</sup> and Binghai Yan<sup>1,\*</sup><sup>1</sup>*Department of Condensed Matter Physics, Weizmann Institute of Science, Rehovot 7610001, Israel*<sup>2</sup>*Center for Nanochemistry, Beijing Sciences and Engineering Centre for Nanocarbons, College of Chemistry and Molecular Engineering, Peking University, Beijing 100871, China*

(Received 28 March 2018; revised manuscript received 11 June 2018; published 25 June 2018)

Recently, an air-stable layered semiconductor  $\text{Bi}_2\text{O}_2\text{Se}$  was discovered to exhibit an ultrahigh mobility in transistors fabricated with its thin layers. In this work, we explored the mechanism that induces the high mobility and distinguishes  $\text{Bi}_2\text{O}_2\text{Se}$  from other semiconductors. We found that the electron donor states lie above the lowest conduction band. Thus, electrons get spontaneously ionized from donor sites (e.g., Se vacancies) without involving the thermal activation, different from the donor ionization in conventional semiconductors. Consequently, the resistance decreases as reducing the temperature as observed in our measurement, which is similar to a metal but contrasts to a usual semiconductor. Furthermore, the electron conduction channels locate spatially away from ionized donor defects (Se vacancies) in different van der Waals layers. Such a spatial separation can strongly suppress the scattering caused by donor sites and subsequently increase the electron mobility, especially at the low temperature. We call this high-mobility mechanism self-modulation doping, i.e., the modulation doping spontaneously happening in a single-phase material without requiring a heterojunction. Our work paves a way to design high-mobility semiconductors with layered materials.

DOI: [10.1103/PhysRevB.97.241203](https://doi.org/10.1103/PhysRevB.97.241203)

High-mobility devices and materials are significant for both fundamental research and semiconductor technology. A well-known method to realize the high mobility is the modulation doping based on a heterostructure that spatially separates carrier from ionized impurities [1]. This mechanism was also theoretically proposed to design highly conductive semiconductor nanowires recently [2,3]. In recent years, two-dimensional (2D) materials including graphene [4–9] and three-dimensional topological semimetals [10,11] provide new high-mobility platforms with ultrafast Dirac electrons. Very recently, an emerging layered semiconductor, bismuth oxychalcogenide ( $\text{Bi}_2\text{O}_2\text{Se}$ ), was found to exhibit ultrahigh electron mobility and strong quantum oscillations in fabricated devices [12]. Soon this material was fabricated into ultrafast, highly sensitive infrared photodetectors [13] and magnetoresistance devices [14], and was predicted to be a candidate for the ferroelectric property [15].

The  $\text{Bi}_2\text{O}_2\text{Se}$  compound attracts great research attention for designing novel devices, while the fundamental origin of its high mobility remains unexplored. Similar layered chalcogenides, such as the well-known topological insulator [16,17]  $\text{Bi}_2\text{Se}_3$ , usually suffer from the self-doping (e.g., Se vacancies) and exhibit very low mobility [18–20]. Furthermore, the resistance of a usual semiconductor decreases on increasing the temperature [21], because free carriers require the thermal energy to get ionized from donor/acceptor sites. In contrast, the resistance of  $\text{Bi}_2\text{O}_2\text{Se}$  exhibits an opposite trend to the temperature [12,22]. In addition, such a temperature dependence of the resistance is reminiscent of a similar trend observed in  $\text{SrTiO}_3$  [23,24]. The uniqueness of this material

motivates us to investigate its electronic structure to understand its transport properties.

In ordinary semiconductors, it is known as the defect states are normally located in the band gap and lower than the empty conduction bands as shown in Fig. 1(a). In order to achieve the conducting channels, the excess electrons should be excited to the next conduction band by temperature. Free electrons display the higher density at a higher temperature and thus, the resistance will decrease sharply with increasing temperature. In contrast,  $\text{Bi}_2\text{O}_2\text{Se}$  samples exhibit a different  $R$ - $T$  dependence from ordinary semiconductors [see Fig. 1(b)].

In this Rapid Communication, we have performed experimental and theoretical studies on the electronic and transport properties of  $\text{Bi}_2\text{O}_2\text{Se}$ . We have found that Se vacancies ( $V_{\text{Se}}$ ) and Se-Bi antisites ( $\text{Se}_{\text{Bi}}$ ) are crucial donors for electron carriers in this material. Because the  $V_{\text{Se}}$  distributes in the Se layer while the wave function of conduction electrons locates in the  $\text{Bi}_2\text{O}_2$  layer in the lattice, the scattering of  $V_{\text{Se}}$  to electron carriers is much weaker. However,  $\text{Se}_{\text{Bi}}$  scatters electrons strongly, since it distributes in the same  $\text{Bi}_2\text{O}_2$  layer as the conduction band [Fig. 1(c)]. Interestingly, as evidenced by the formation energy calculations, the relative amount of  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  can be readily adjusted by changing the Se richness during synthesis.  $V_{\text{Se}}$  is the major defect in the Se-poor condition while  $\text{Se}_{\text{Bi}}$  is the major one in the Se-rich condition, which well explained the low-temperature mobility variation of  $\text{Bi}_2\text{O}_2\text{Se}$  synthesized under different Se-richness conditions. Further, we found that the donor levels of both  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  lie above the conduction-band bottom in energy by calculations. Such a band structure induces the automatic ionization of free electrons from these defects without overcoming an activation barrier [Fig. 1(b)]. It explains the metal-like temperature dependence of the resistance measured.

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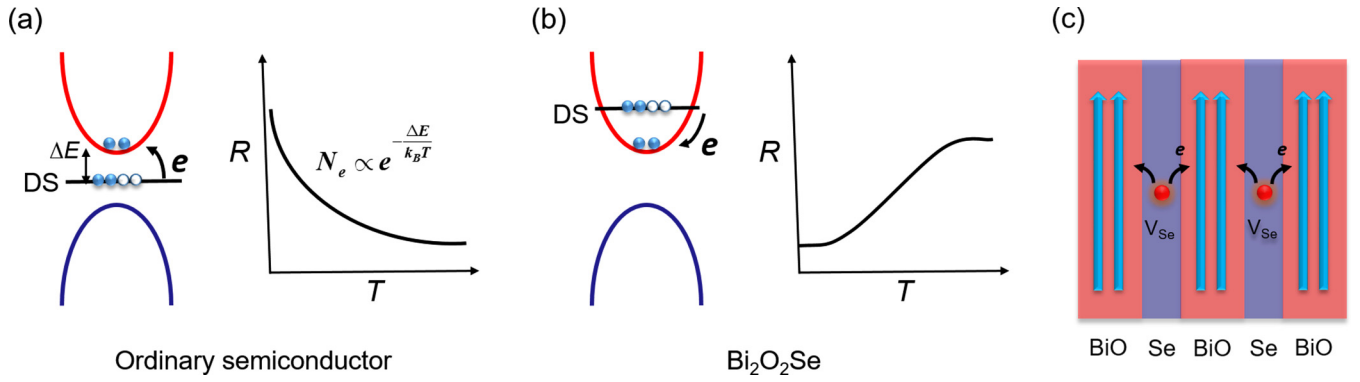


FIG. 1. Energy level for defect state (DS), electron-doping process, and temperature-dependent resistance for ordinary semiconductors (a) and  $\text{Bi}_2\text{O}_2\text{Se}$  (b). (c) Diagram of spatial separation between conducting channels and donor vacancies ( $V_{\text{Se}}$ ) in  $\text{Bi}_2\text{O}_2\text{Se}$ .

In the Se-richness-controlled chemical vapor deposition growth experiments [29], we found there are two types of 2D  $\text{Bi}_2\text{O}_2\text{Se}$  samples with obviously distinct transport performances under different Se-richness growth conditions. The Se/Bi ratio is controlled by adjusting the ratio of  $\text{Bi}_2\text{Se}_3$  and  $\text{Bi}_2\text{O}_3$  that were used as coevaporation sources (i.e., keep the amount of  $\text{Bi}_2\text{O}_3$  constant, while changing the amount of  $\text{Bi}_2\text{Se}_3$  independently). As shown in Figs. 2(a) and 2(b), both the Se-poor and Se-rich samples show a metal-like  $R$ - $T$  behavior, namely, longitudinal resistance ( $R_{xx}$ ) decreases monotonously upon cooling down. This  $R$ - $T$  feature is dif-

ferent from the ordinary semiconductor, whose resistance usually increases sharply upon cooling down [see Fig. 1(a), for example]. Remarkably, the  $\text{Bi}_2\text{O}_2\text{Se}$  samples synthesized under different Se richness show significant differences on residual resistance ratio (RRR, defined as  $R_{xx, 300\text{K}}/R_{xx, 2\text{K}}$ ), which is a key parameter to reflect the intrinsic quality of samples obtained. As shown in Figs. 2(a) and 2(b), the typical RRR of Se-poor  $\text{Bi}_2\text{O}_2\text{Se}$  (67.6) is about an order of magnitude higher than the Se-rich one (7.2). A higher RRR usually indicates a higher Hall mobility. Figures 2(c) and 2(d) show the evolution of Hall mobility and carrier density

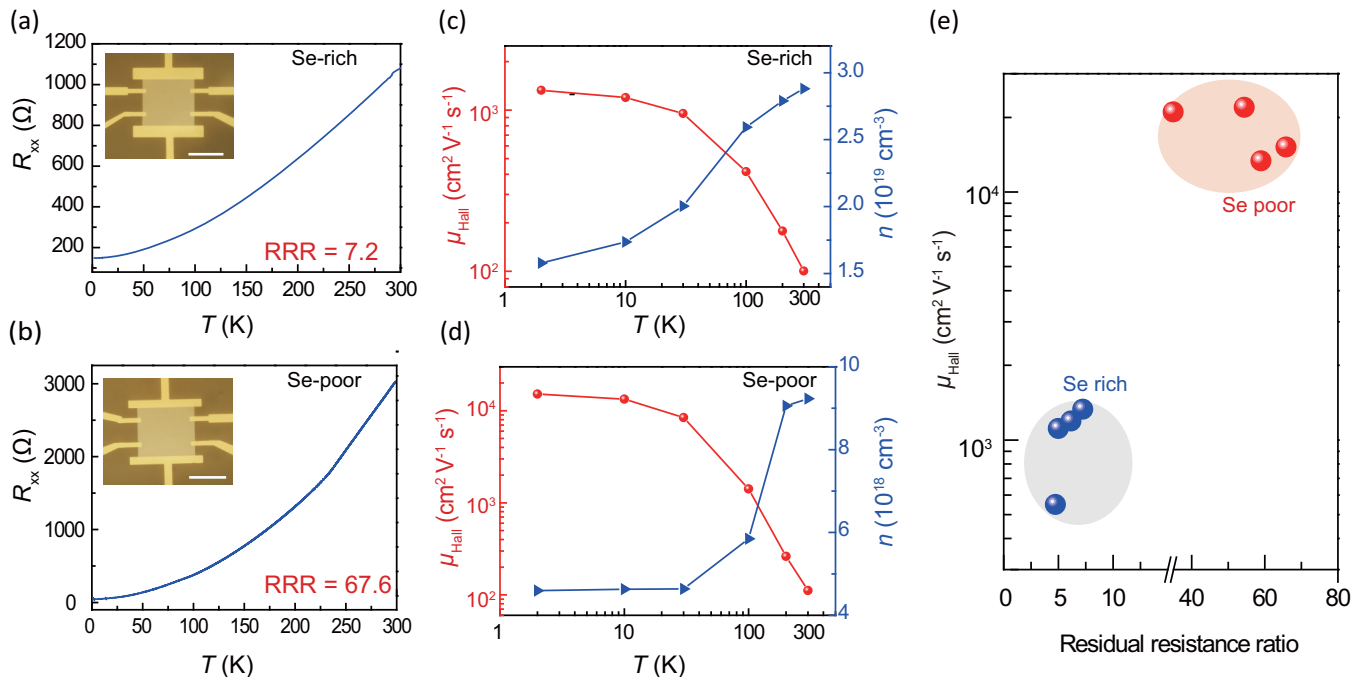


FIG. 2. Electrical measurements of 2D  $\text{Bi}_2\text{O}_2\text{Se}$  crystals synthesized under different Se-richness growth conditions. (a), (b) Typical temperature-dependence longitudinal resistance ( $R_{xx}$ ) of 2D  $\text{Bi}_2\text{O}_2\text{Se}$  crystals synthesized under relatively Se-rich (a) and Se-poor (b) conditions, showing significant difference on residual resistance ratios (RRRs). The Se richness is controlled by adjusting the ratio of  $\text{Bi}_2\text{Se}_3$  and  $\text{Bi}_2\text{O}_3$  that were used as coevaporation sources (i.e., keep the amount of  $\text{Bi}_2\text{O}_3$  constant, while changing the amount of  $\text{Bi}_2\text{Se}_3$  independently). Inset: optical microscope images of  $\text{Bi}_2\text{O}_2\text{Se}$  Hall-bar devices fabricated on mica substrate. Both  $\text{Bi}_2\text{O}_2\text{Se}$  devices have a similar thickness of 10 nm. Scale bar:  $50\ \mu\text{m}$ . (c), (d) The corresponding temperature-dependence Hall mobility ( $\mu_{\text{Hall}}$ ) and carrier density ( $n$ ) of 2D  $\text{Bi}_2\text{O}_2\text{Se}$  crystals synthesized under relatively Se-rich (c) and Se-poor (d) conditions. (e) Statistics for low-temperature Hall mobility (2 K) and residual resistance ratios of 2D  $\text{Bi}_2\text{O}_2\text{Se}$  crystals synthesized under different Se-richness growth condition. Much higher Hall mobility and residual resistance ratio were obtained on  $\text{Bi}_2\text{O}_2\text{Se}$  crystals synthesized under a relatively Se-poor condition.

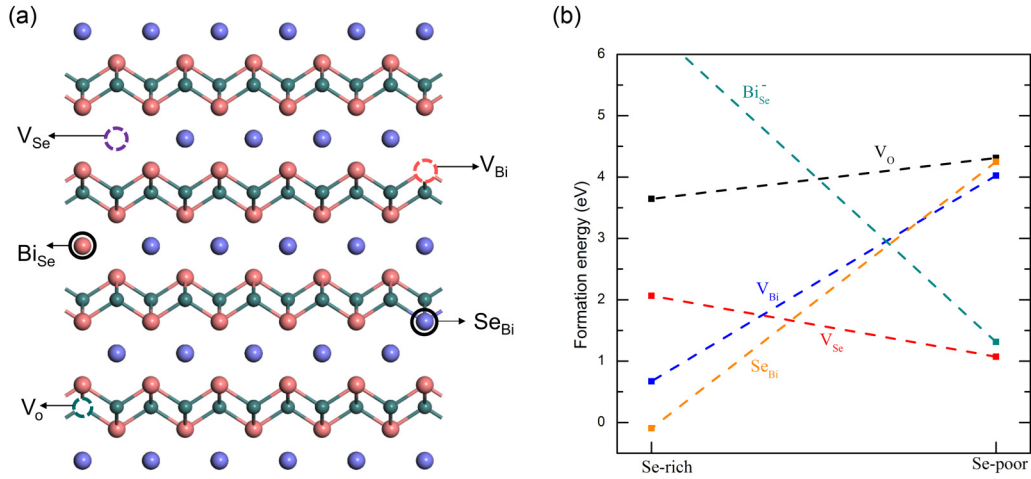


FIG. 3. (a) Atomic structure of Bi<sub>2</sub>O<sub>2</sub>Se with five possible defects. (b) The formation energy for these defects with respect to the chemical potential at different Se-richness conditions.

as a function of temperature. The Hall mobility ( $\mu_{\text{Hall}}$ ) is obtained from  $\mu_{\text{Hall}} = (L/W)(G/ne)$ , where  $e$  is the charge of an electron and  $n$  is the 2D charge density determined from Hall coefficient  $R_{\text{H}}$  measurements ( $n = 1/eR_{\text{H}}$ ). Remarkably, the Hall mobility of both Se-rich and Se-poor samples increased monotonously as the temperature cools down to 2 K, and this feature fits well with a phonon-dominated charge transport mechanism. Interestingly, the Se-poor sample holds a significantly higher Hall mobility ( $>15\,000\text{ cm}^2\text{ V}^{-1}\text{ s}^{-1}$ ) than the Se-rich sample ( $\sim 1000\text{ cm}^2\text{ V}^{-1}\text{ s}^{-1}$ ) at 2 K, while showing a similar room-temperature Hall mobility. It can be well explained by taking into consideration that the charge impurities (defects) scattering usually dominate the scattering events at low temperature, while phonon scattering dominates at room temperature [25–27]. In other words, our experimental results suggest, to some extent, the existence of some kinds of defects that may greatly depress the mobility of Se-rich Bi<sub>2</sub>O<sub>2</sub>Se. To further confirm this feature, we performed the statistics for low-temperature Hall mobility (2 K) and residual resistance ratios of 2D Bi<sub>2</sub>O<sub>2</sub>Se crystals synthesized under different Se-richness growth condition [Fig. 2(e)]. Obviously, the Se-poor samples indeed show much higher mobility and residual resistance ratio than the Se-rich one.

To understand the origin of unusual resistance behavior and the high mobility, we have performed first-principles calculations [28] to explore the structural and electronic properties of Bi<sub>2</sub>O<sub>2</sub>Se in the following. We first estimate the formation of possible defects as potential donors and acceptors with respect to the experimental condition. The free carriers in Bi<sub>2</sub>O<sub>2</sub>Se are expected to come from lattice defects, since there are no specific impurities introduced in the experiment. As shown by the atomic configuration displayed in Fig. 3(a), Bi<sub>2</sub>O<sub>2</sub>Se exhibits a layered crystal structure consisting of alternate Bi<sub>2</sub>O<sub>2</sub> layers and Se layers. The Bi-Se distance in Bi<sub>2</sub>O<sub>2</sub>Se is 3.28 Å, longer than the strong covalent bond length of 2.84–3.05 Å in Bi<sub>2</sub>Se<sub>3</sub>. This suggests that the Bi<sub>2</sub>O<sub>2</sub> and Se layers are combined with relatively weak electrostatic interaction. Five possible defects are considered here: Se vacancies ( $V_{\text{Se}}$ ), Bi vacancies ( $V_{\text{Bi}}$ ), O vacancies ( $V_{\text{O}}$ ), Se antisites at Bi positions ( $\text{Se}_{\text{Bi}}$ ), and Bi antisites at Se positions ( $\text{Bi}_{\text{Se}}$ ), as illustrated

in Fig. 3(a). The defect formation energies are calculated for the Se-rich and Se-poor conditions, as displayed in Fig. 3(b). The chemical potential of the Se element at the Se-rich limit refers to the one in bulk Se, while the chemical potential of Se in Bi<sub>2</sub>Se<sub>3</sub> is taken into consideration for the Se-poor limit [29]. Among the five types of defects,  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  present the lowest formation energies at the Se-poor and Se-rich conditions, respectively. This indicates that  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  are probably the dominant defects in general. Because of the large slope of the  $\text{Se}_{\text{Bi}}$  formation energy [Fig. 3(b)], the existence of  $\text{Se}_{\text{Bi}}$  is expected to be strongly suppressed in the Se-poor condition. In short,  $V_{\text{Se}}$  is the major defect in the Se-poor condition while  $\text{Se}_{\text{Bi}}$  is the major one in the Se-rich condition.

Next, we investigate the roles of  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  in doping the semiconductor Bi<sub>2</sub>O<sub>2</sub>Se. Figure 4 shows band structures of the pristine bulk and those with  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  defects. We choose a  $5 \times 5 \times 2$  bulk supercell that contains 500 atoms to simulate the doping effect of a single defect, to suppress the interaction of defects from neighboring supercells. The pristine bulk presents an energy gap. The existence of both  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  shift the Fermi energy up into the conduction bands. In contrast to the doping effect of a conventional semiconductor [illustrated in Fig. 1(a)], both defects do not induce any in-gap donor states in the band structure. Corresponding donor states lie about 0.8 eV above the conduction-band bottom. Each  $V_{\text{Se}}$  ( $\text{Se}_{\text{Bi}}$ ) site donates two (one) electrons to the bulk, consistent with the shifted Fermi energy position. In addition, we note that the 0.32 eV indirect gap of Bi<sub>2</sub>O<sub>2</sub>Se is underestimated by the density-functional theory (DFT). But the positions of  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  with respect to the conduction band are not affected by the DFT band gap. Similarly,  $V_{\text{Bi}}$  and  $V_{\text{O}}$  are found to be acceptors with acceptor levels in the valence bands [29]. The fact that  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  are dominant for different Se richness indicates corresponding samples are electron doped, well consistent with our experimental observation.

Because the donor states caused by  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  are higher in energy than the conduction-band bottom, excess electrons spontaneously move from donor states to the conduction band without requiring thermal activation. Therefore, the resultant electron carrier density does not increase exponentially with

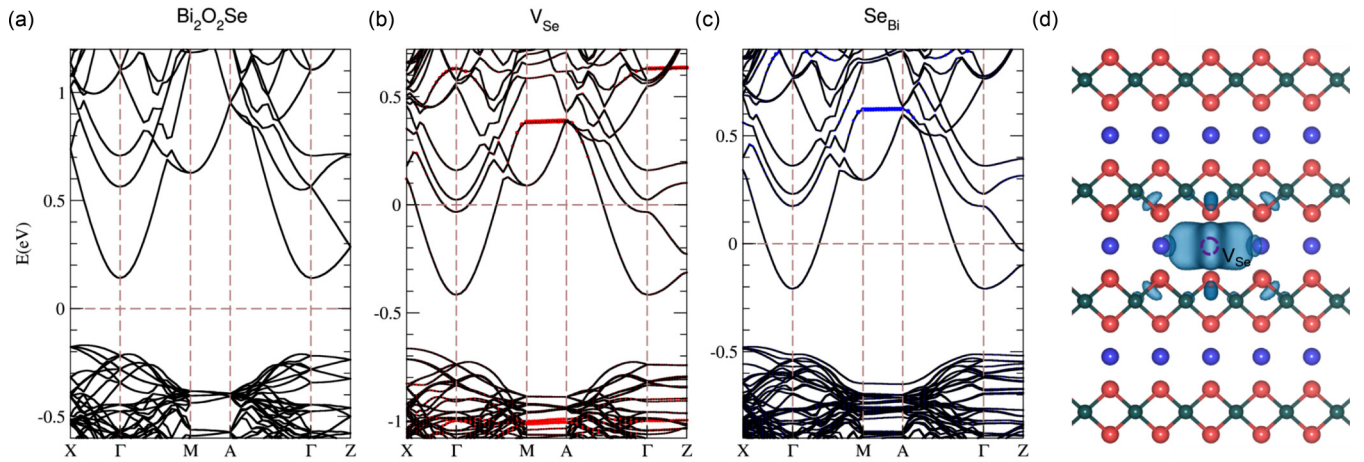


FIG. 4. Calculated band structures of (a) perfect  $\text{Bi}_2\text{O}_2\text{Se}$  and the configurations with domain defects (b)  $V_{\text{Se}}$  and (c)  $\text{Se}_{\text{Bi}}$  antisite. Fermi level is set at 0. In (b), the red and blue dots, respectively, present the projected bands on the nearest neighbor Bi and Se atoms close to the  $V_{\text{Se}}$ . In (c), the blue dots denote the states located on the Se atom which is on a site previously occupied by a Bi atom. (d) The charge density distribution for the  $V_{\text{Se}}$  defect state marked by the filled purple circle in (b) at the  $M$   $k$  point. The isosurface of the charge density corresponds to  $0.0015 e/\text{\AA}^3$ .

increasing temperature, i.e.,  $N_e \propto e^{-\Delta E/k_B T}$ , where  $\Delta E$  is the activation energy. Instead, the carrier density shows weak dependence on the temperature. It is consistent with the fact that the carrier density remains in the same order of magnitude from 2 to 300 K, for both Se-rich and Se-poor samples [see Figs. 2(b) and 2(d)]. Further, it also well explains that  $R_{xx}$ - $T$  behavior of  $\text{Bi}_2\text{O}_2\text{Se}$  is similar to a metal rather than a semiconductor. With reducing the temperature, the decreasing resistance is mainly caused by the quickly increasing mobility.

Additionally, we can rationalize the high energy of the  $V_{\text{Se}}$  state in the band structure by some chemical intuition. The  $\text{Bi}_2\text{O}_2\text{Se}$  lattice can be viewed as stacking  $\text{Se}^{2-}$  and  $(\text{Bi}_2\text{O}_2)^{2+}$  layers alternatively. The  $\text{Se}^{2-}$  and  $(\text{Bi}_2\text{O}_2)^{2+}$  layers bind together by ionic-like bonds, different from an ordinary covalent semiconductor. It is hard for the  $V_{\text{Se}}$  to trap a free electron because of the strong electrostatic repulsion inside the negative-charge-carried  $\text{Se}^{2-}$  layer. This leads to the much higher energy of the vacancy level as revealed by our calculations.

Furthermore, we discuss different roles of  $V_{\text{Se}}$  and  $\text{Se}_{\text{Bi}}$  in the electron mobility. Recall that the wave function of the lowest conduction band distributes predominantly inside the  $\text{Bi}_2\text{O}_2$  layer;  $V_{\text{Se}}$  defect states that locate in the Se layer [see Fig. 4(d)] are spatially separated from the conducting electrons. Consequently, the scattering due to the ionized donor sites is suppressed, giving rise to the large mobility at low temperature. Here, the separation of donor sites and free electrons are naturally realized in a single-phase material, leading to the same effect as the modulation doping. Thus, we refer to the

high-mobility mechanism in  $\text{Bi}_2\text{O}_2\text{Se}$  as the self-modulation doping. For the other donor  $\text{Se}_{\text{Bi}}$ , the conducting channels are strongly disrupted because  $\text{Se}_{\text{Bi}}$  sites locate inside the same  $\text{Bi}_2\text{O}_2$  layers, inducing much lower mobility than the  $V_{\text{Se}}$  case. Therefore, the spatial distribution of two defects explains the large mobility variation between samples from the Se-poor ( $V_{\text{Se}}$ -dominated, high-mobility) and Se-rich ( $\text{Se}_{\text{Bi}}$ -dominated, low-mobility) conditions. In addition, we should note that the 2D layered structure is the precondition for the large separation of conduction electrons and the ionized defects. It is different from the case of the three-dimensional material  $\text{SrTiO}_3$ .

In conclusion, combing the experimental measurements and first-principles calculations, we have found that the self-modulation doping mechanism in the layered  $\text{Bi}_2\text{O}_2\text{Se}$  semiconductor leads to the high electron mobility. Our work also explains the unusual metal-like resistance-temperature dependence of  $\text{Bi}_2\text{O}_2\text{Se}$ . Our findings pave a way to design high-mobility semiconductors in emerging layered materials.

B.H.Y. is supported by a research grant from the Benozio Endowment Fund for the Advancement of Science. H.L.P. and J.X.W. acknowledge financial support from the National Basic Research Program of China (Grants No. 2014CB932500, No. 2016YFA0200101, and No. 2014CB920900), the National Natural Science Foundation of China (Grants No. 21733001, No. 21525310, and No. 11774010), and a China Postdoctoral Science Foundation funded project.

H.F. and J.W. contributed equally to this work.

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